

Fröhlich modes in porous III–V semiconductors

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Received 7 March 2001, in final form 15 May 2001

Published 19 July 2001

Online at stacks.iop.org/JPhysCM/13/6687

Abstract

Porous GaP, InP and GaAs structures fabricated by MeV ion-implantation-assisted electrochemical etching were investigated by Raman and Fourier transform infrared spectroscopy. Fröhlich modes in the frequency gap between the transverse optical and longitudinal optical frequencies were observed and their longitudinal–transverse splitting was established. The frequency-dependent optical properties in the infrared region were calculated using a dielectric function derived on the basis of an appropriate two-dimensional effective-medium theory. The theoretical reflectance spectra are found to be in good agreement with the experimental ones and the predicted coupled Fröhlich–plasmon modes for conducting samples were observed experimentally. The wavelength used in Raman measurements did not fulfil the requirements of effective-medium theory, but the resulting spectra could be explained at least qualitatively by taking into account the diffuse scattering.

1. Introduction

Increasing attention has been paid in recent years to the study of the properties inherent to porous materials. In addition to porous silicon, widely investigated by a variety of different means [1, 2], porous III–V semiconductor compounds have aroused increasing interest [3–9] due to their potential applications in the field of electronics and photonics [10].